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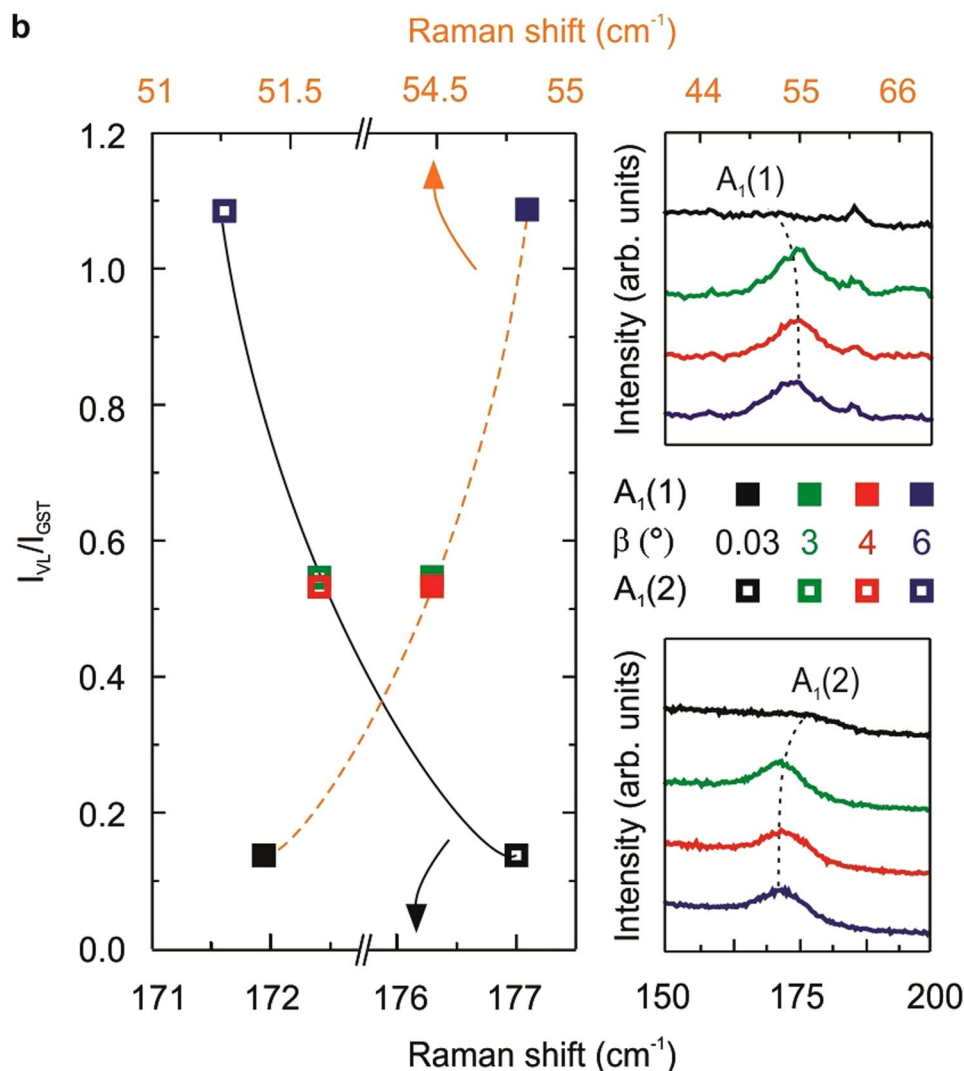
## **Author Correction:** Modulation of van der Waals and classical epitaxy induced by strain at the Si step edges in GeSbTe alloys

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This Article contains errors in Figure 4b. The colours of the curves in the left panel were inadvertently switched. The correct Figure 4b appears below as Figure 1.

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**Figure 1.** Stable rhombohedral stacking with almost pure GST124 on substrate miscut. **(a)** Raman spectra of 70 nm-thick GST grown on Si (111) with  $\beta = 0.03^\circ$  at RT (black),  $\beta = 4^\circ$  at RT (red) and  $\beta = 4^\circ$  at 10 K (dark red). **(b)** Intensity ratio of the second order XRD for the VL peak and GST peak ( $I_{\text{VL}}/I_{\text{GST}}$ ) as a function of the Raman shift for the  $A_1(1)$  (full squares) and  $A_1(2)$  (empty squares) modes with  $\beta = 0.03^\circ$  (black),  $3^\circ$  (green),  $4^\circ$  (red) and  $6^\circ$  (blue). Dashed and solid lines serve as a guide to the eye. The top and bottom right panels show the Raman shift of the  $A_1(1)$  and  $A_1(2)$  modes, respectively. **(c)** 70 nm- (red) or 7 nm- (light blue) thick GST grown on Si (111) with  $\beta = 4^\circ$ .



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